

JC13 Rec'd PCT/PTO 15 MAR 2002

511.41485X00

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8-16-02IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: T. NARITA, et al.
Serial No: To be assigned
Filed: March 15, 2002
Title: COMPOSITION, METHODS FOR FORMING LOW-PERMITTIVITY FILM USING THE COMPOSITION, LOW-PERMITTIVITY FILM, AND ELECTRONIC PART HAVING THE LOW-PERMITTIVITY FILM

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington DC 20231

March 15, 2002

Sir:

Please amend the above-identified application, prior to calculation of the filing fee, as follows:

IN THE CLAIMS

Please amend the claims original in the application as follows:

15. (Amended) A method for forming a low-permittivity film which comprises applying the composition according to Claim 1 to a substrate to form a composite film comprising the thermally decomposable polymer and the siloxane oligomer evenly compatibilized therewith, and then heating the resulting film to condense the siloxane oligomer and remove the thermally decomposable polymer.

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16. (Amended) A method for forming a low-permittivity film which comprises applying the composition according to Claim 1 to a substrate to form a composite film comprising the thermally decomposable polymer and the siloxane oligomer evenly compatibilized therewith, subsequently conducting a first heating